



PATENT
Customer No. 22,852
Attorney Docket No. 03180.0278

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ryoichi INANAMI et al.

Application No.: 09/817,270

Filed: March 27, 2001

For: EXPOSURE PATTERN DATA
GENERATION APPARATUS
ASSOCIATED WITH STANDARD
CELL LIBRARY AND CHARGED
BEAM EXPOSURE

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) Group Art Unit: 2881
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) Examiner: P. Johnston
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Commissioner for Patents
Washington, DC 20231

Sir:

AMENDMENT

In reply to the Office Action dated December 12, 2002, please amend the
application as follows:

IN THE CLAIMS:

Please amend claims 1, 7, and 15, as follows:

1. (Amended) A charged beam exposure for delineating patterns of a system on
a substrate to describe the system in a logic expression, to convert the logic expression
into a connection of standard cells, and to delineate patterns of the standard cells on the
substrate, comprising:

a beam generation source generating a charged beam;



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